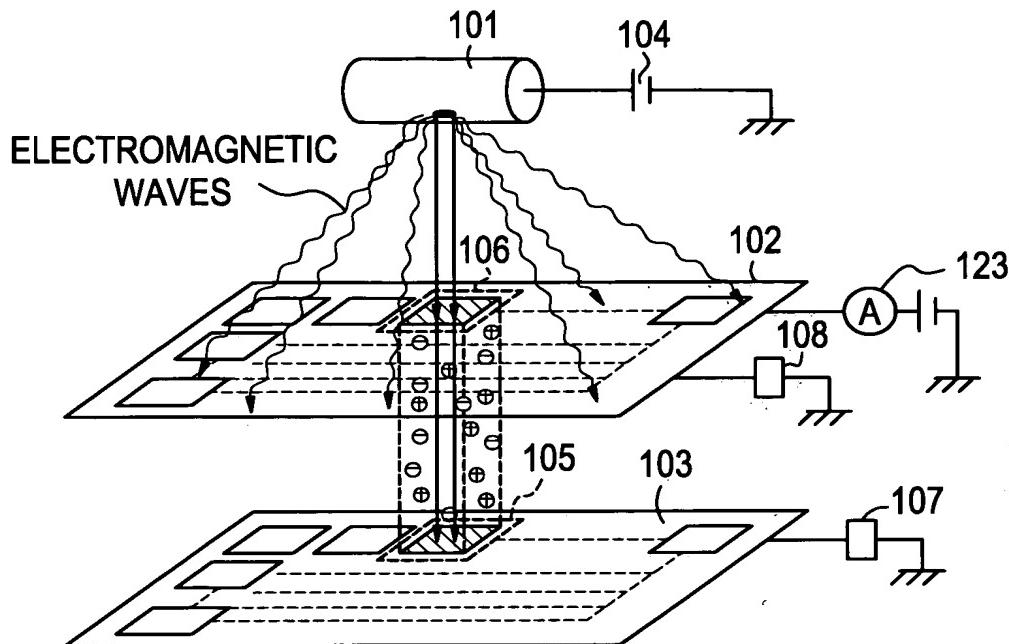


09/866,651



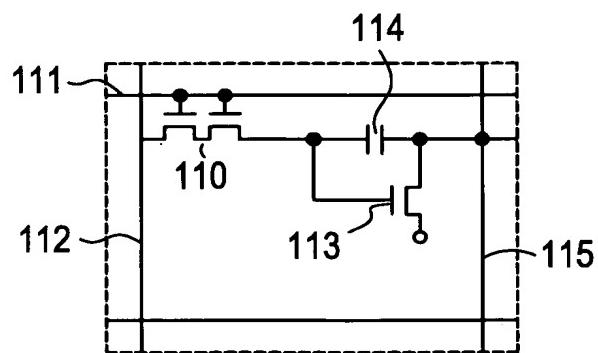
1/18

**FIG. 1A**



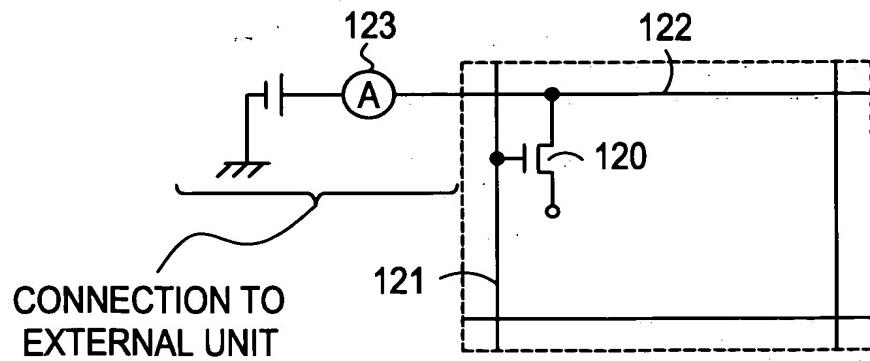
**FIG. 1B**

ENLARGED DIAGRAM OF 105



**FIG. 1C**

ENLARGED DIAGRAM OF 106

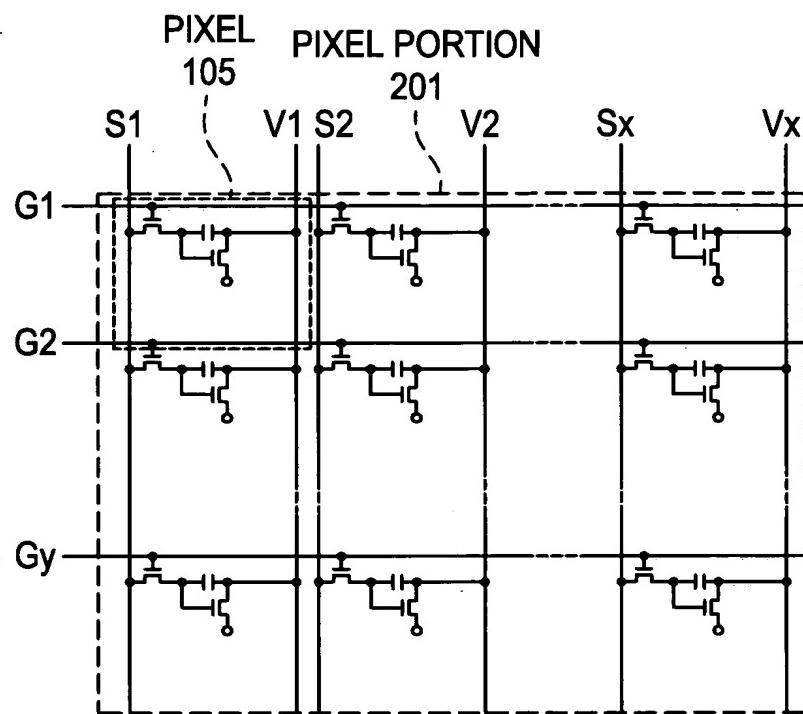




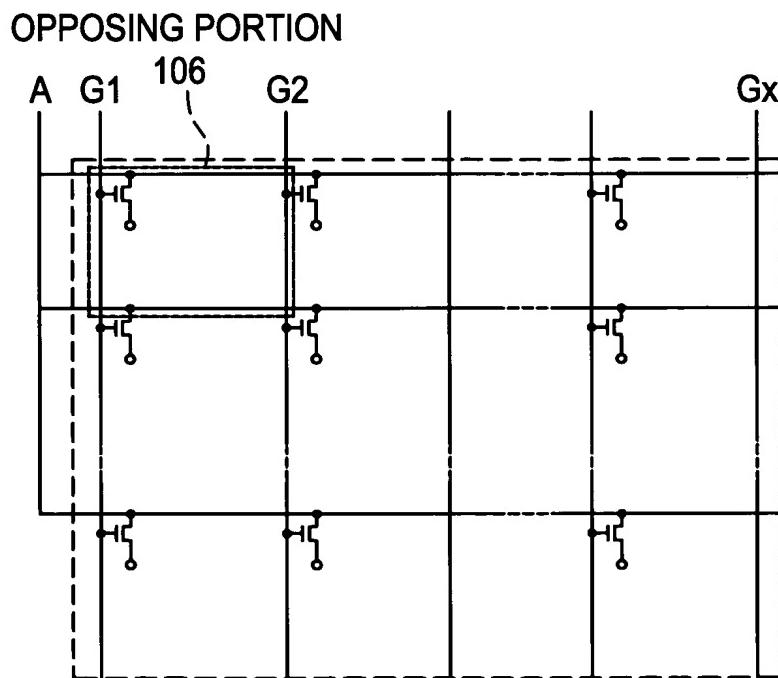
09/866,651

2/18

## FIG. 2A



## FIG. 2B





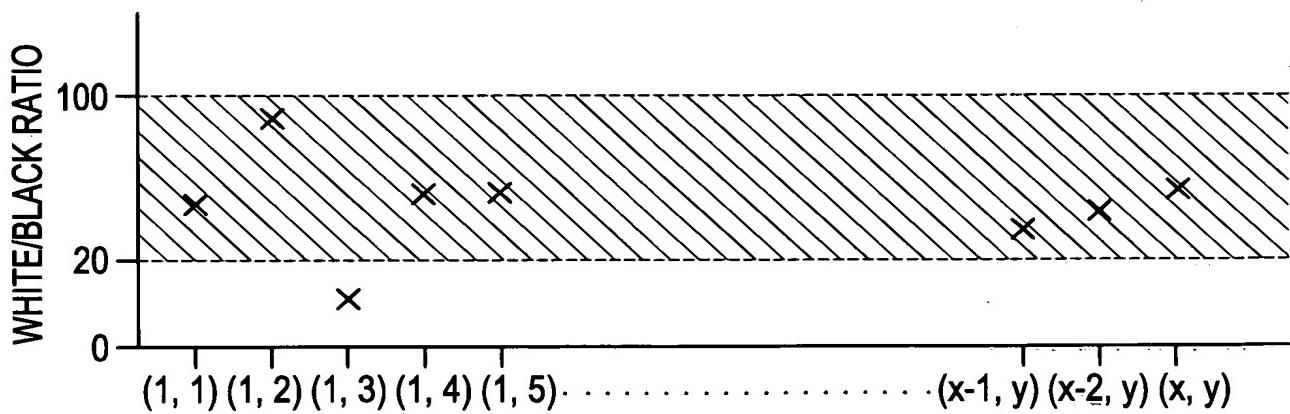
09/866, 651

3/18

**FIG. 3A**

(1, 1)	(2, 1)	(3, 1)	(4, 1)		(x-1, 1)	(x, 1)
(1, 2)	(2, 2)	(3, 2)	(4, 2)		(x-1, 2)	(x, 2)
(1, 3)	(2, 3)	(3, 3)	(4, 3)		(x-1, 3)	(x, 3)
(1, 4)	(2, 4)	(3, 4)	(4, 4)		(x-1, 4)	(x, 4)
(1, y-1)	(2, y-1)	(3, y-1)	(4, y-1)		(x-1, y-1)	(x, y-1)
(1, y)	(2, y)	(3, y)	(4, y)		(x-1, y)	(x, y)

**FIG. 3B**



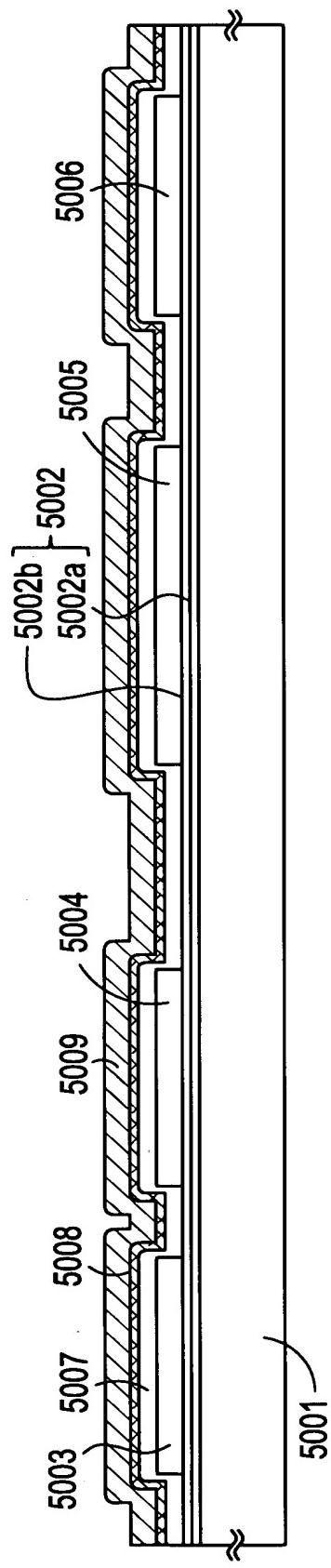


09/866,657

4/18

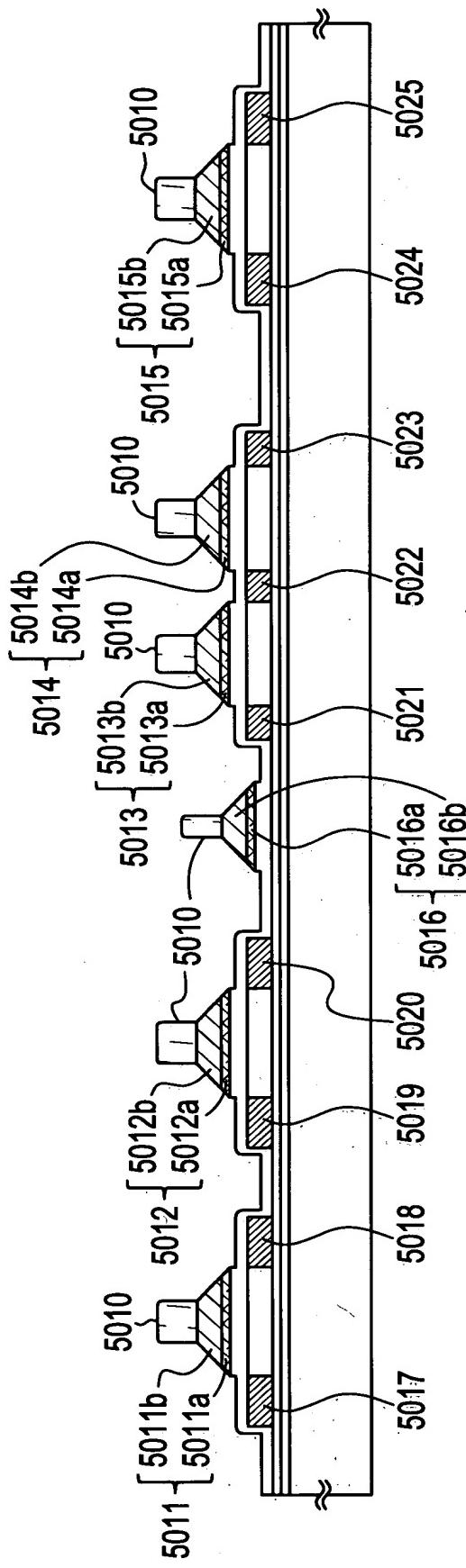
**FIG. 4A**

FORMATION OF ISLAND SEMICONDUCTOR LAYER, GATE-INSULATING FILM,  
AND FIRST AND SECOND CONDUCTING FILMS FOR GATE ELECTRODES



**FIG. 4B**

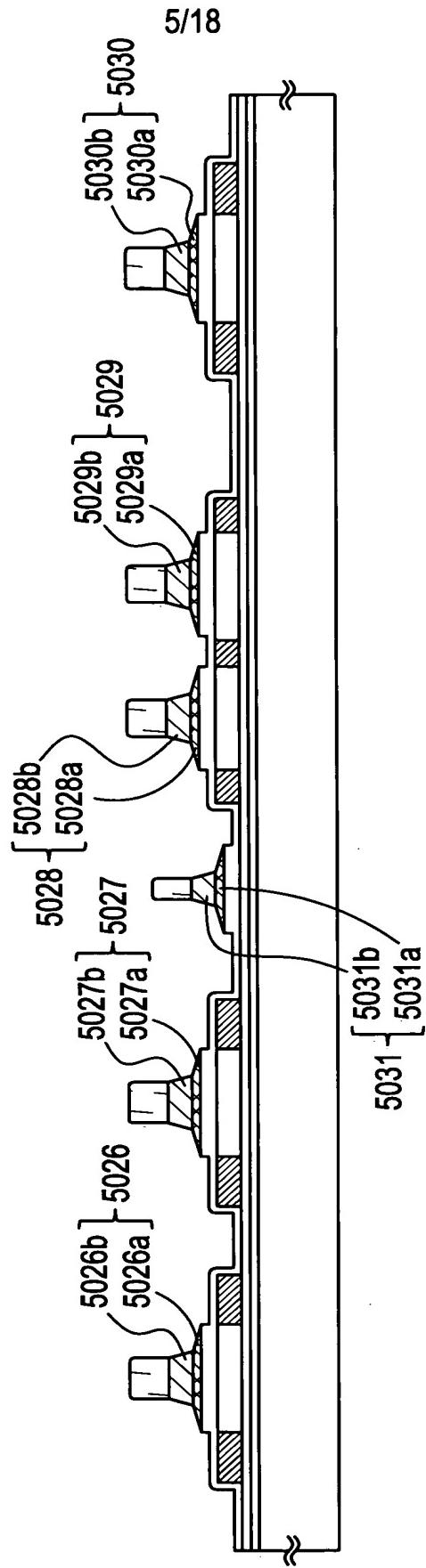
FIRST ETCHING AND FIRST DOPING





09/866, 651

**FIG. 4C**  
SECOND ETCHING

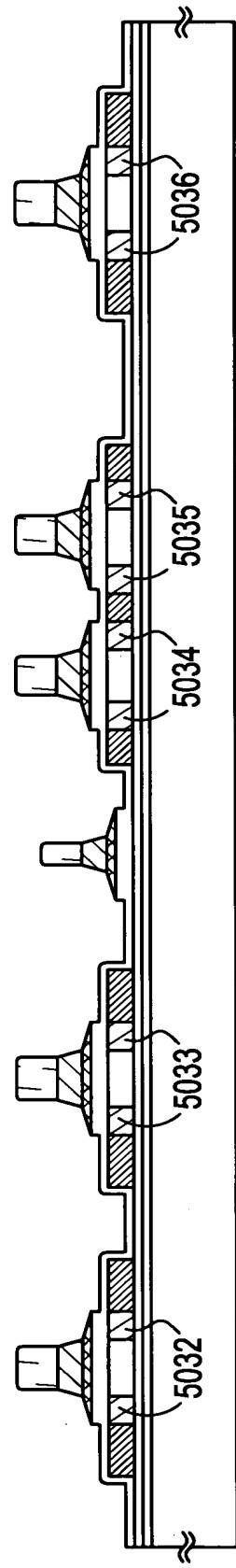




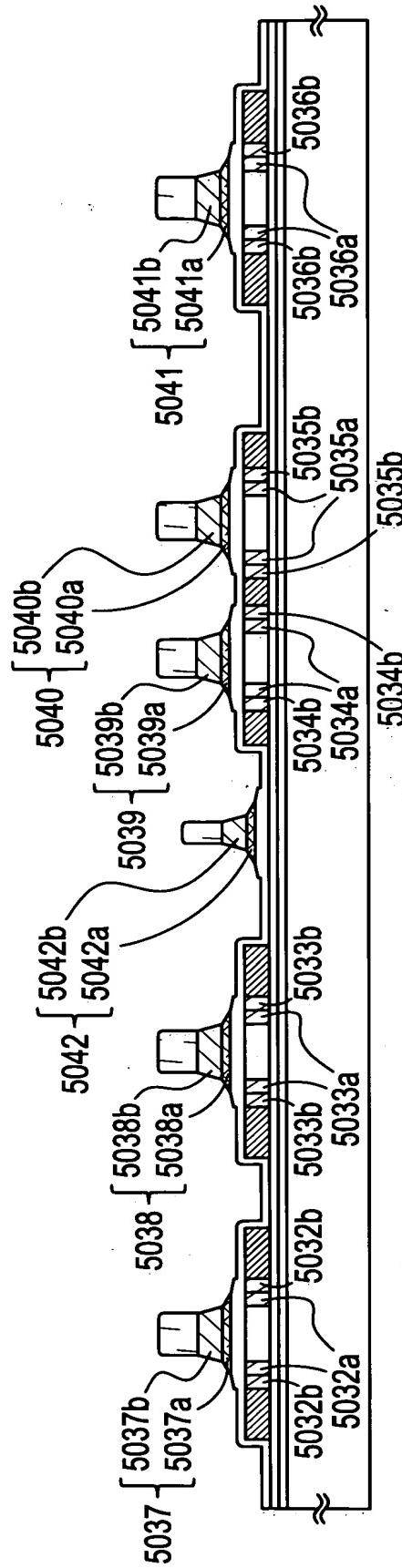
09/866, 651

6/18

**FIG. 5A**  
SECOND DOPING



**FIG. 5B**  
THIRD ETCHING



09/866,651



7/18

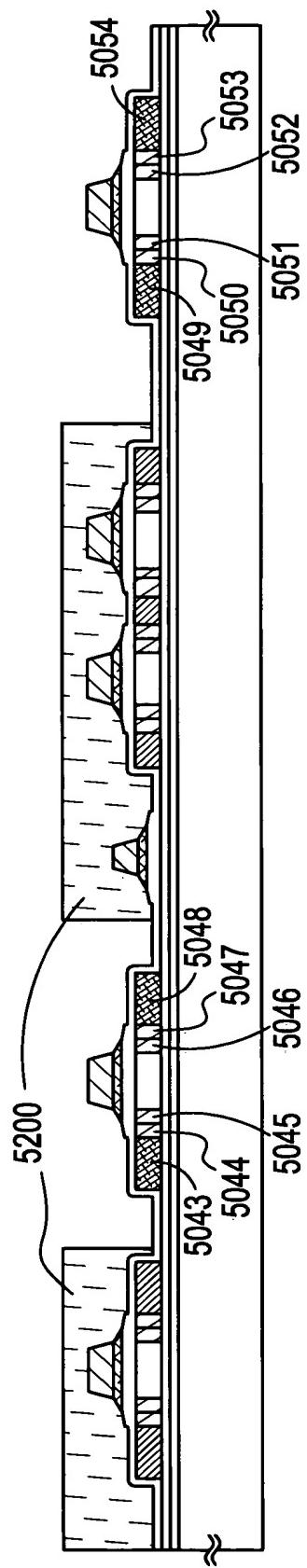


FIG. 5C  
THIRD DOPING

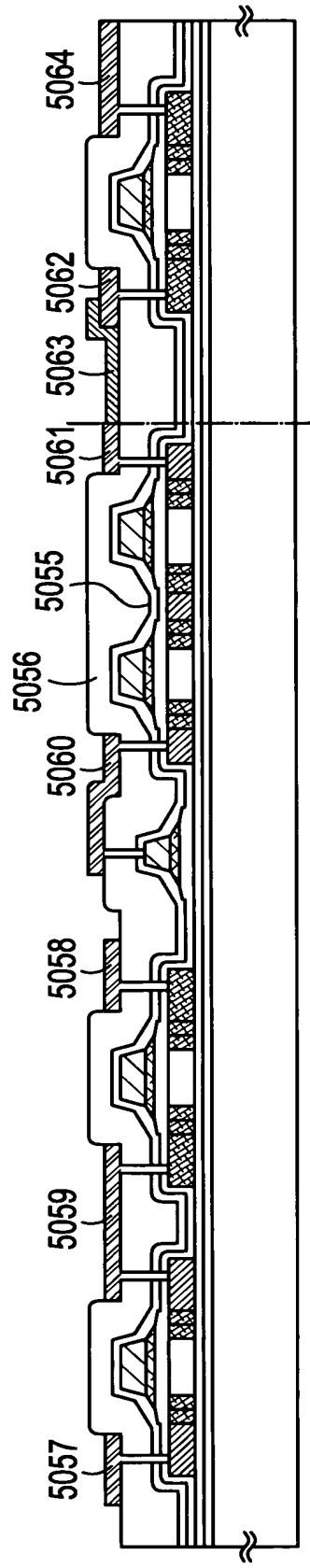


09/866, 657

8/18

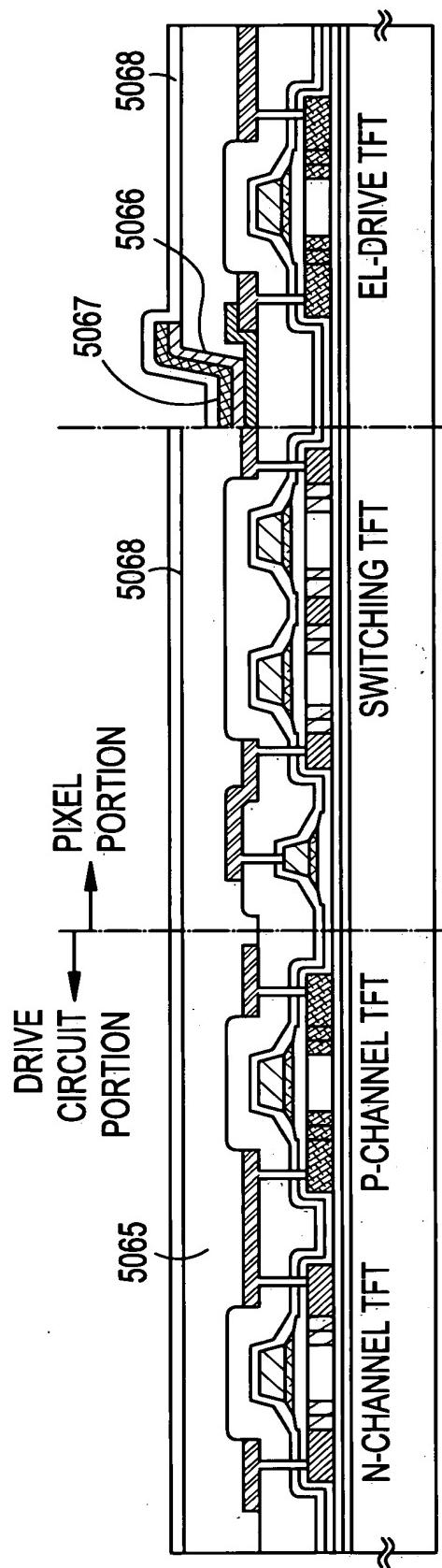
**FIG. 6A**

FORMATION OF THE FIRST AND SECOND INTERLAYER-INSULATING FILMS, WIRINGS AND PIXEL ELECTRODES



**FIG. 6B**

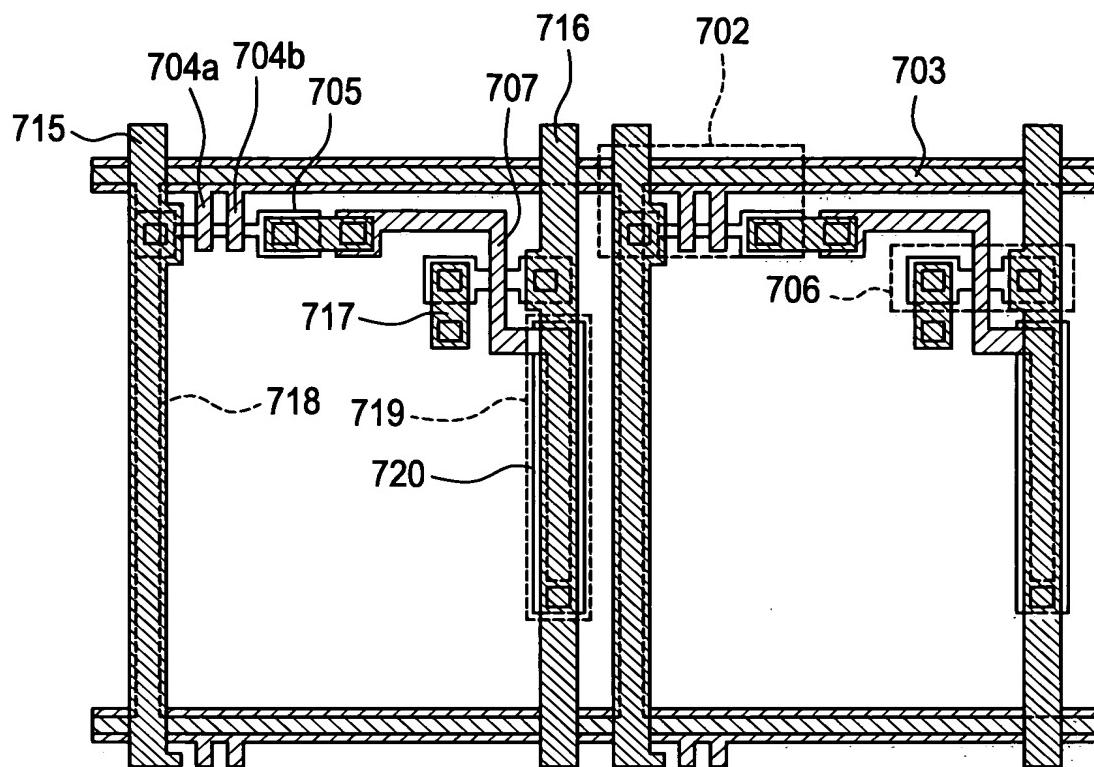
FORMATION OF THE THIRD INTERLAYER-INSULATING FILM, EL LAYER, CATHODES AND PASSIVATION FILM



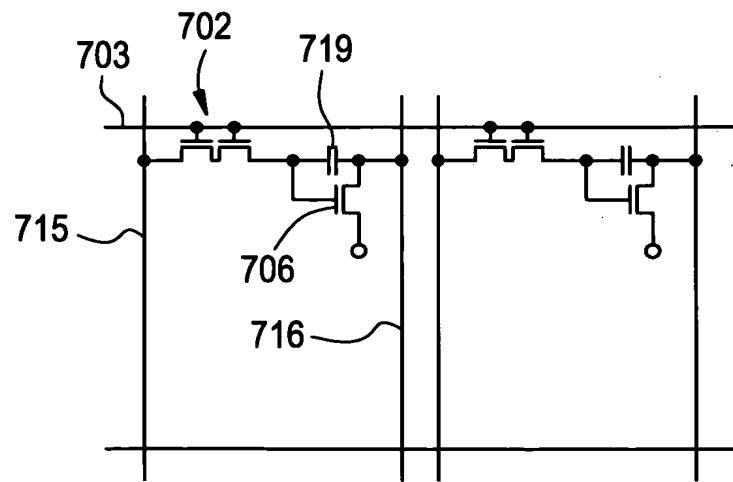
09/866, 651

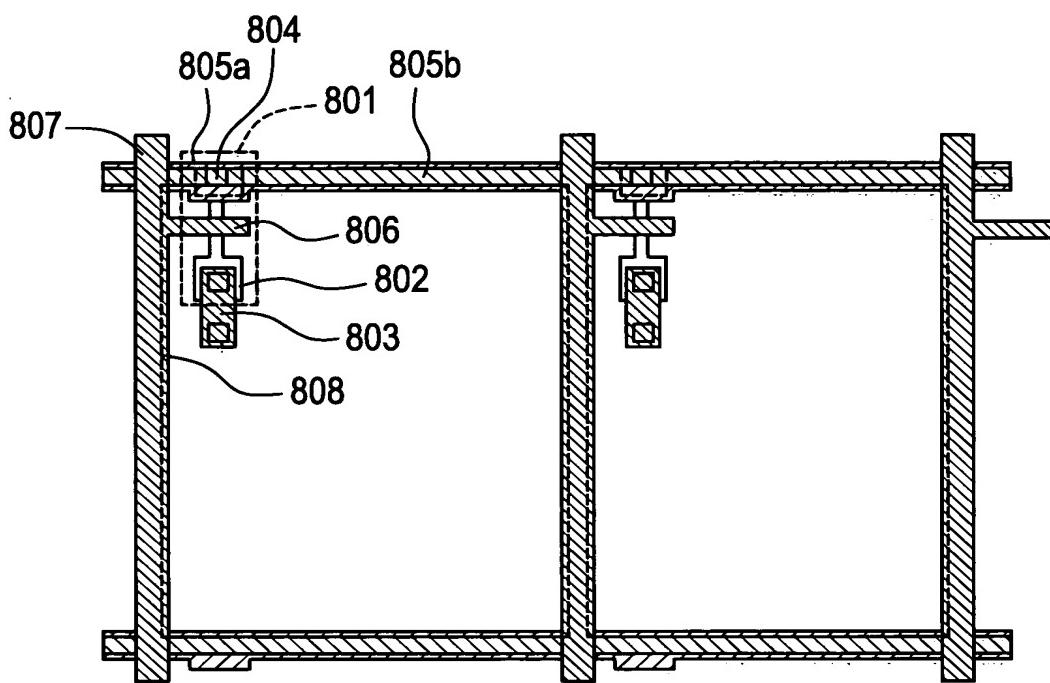
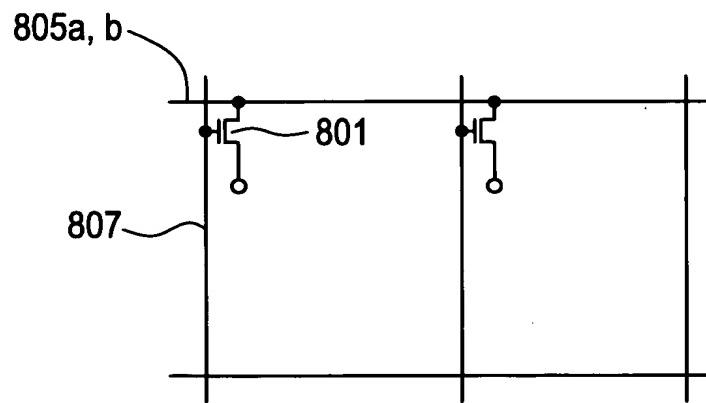
9/18

**FIG. 7A**



**FIG. 7B**

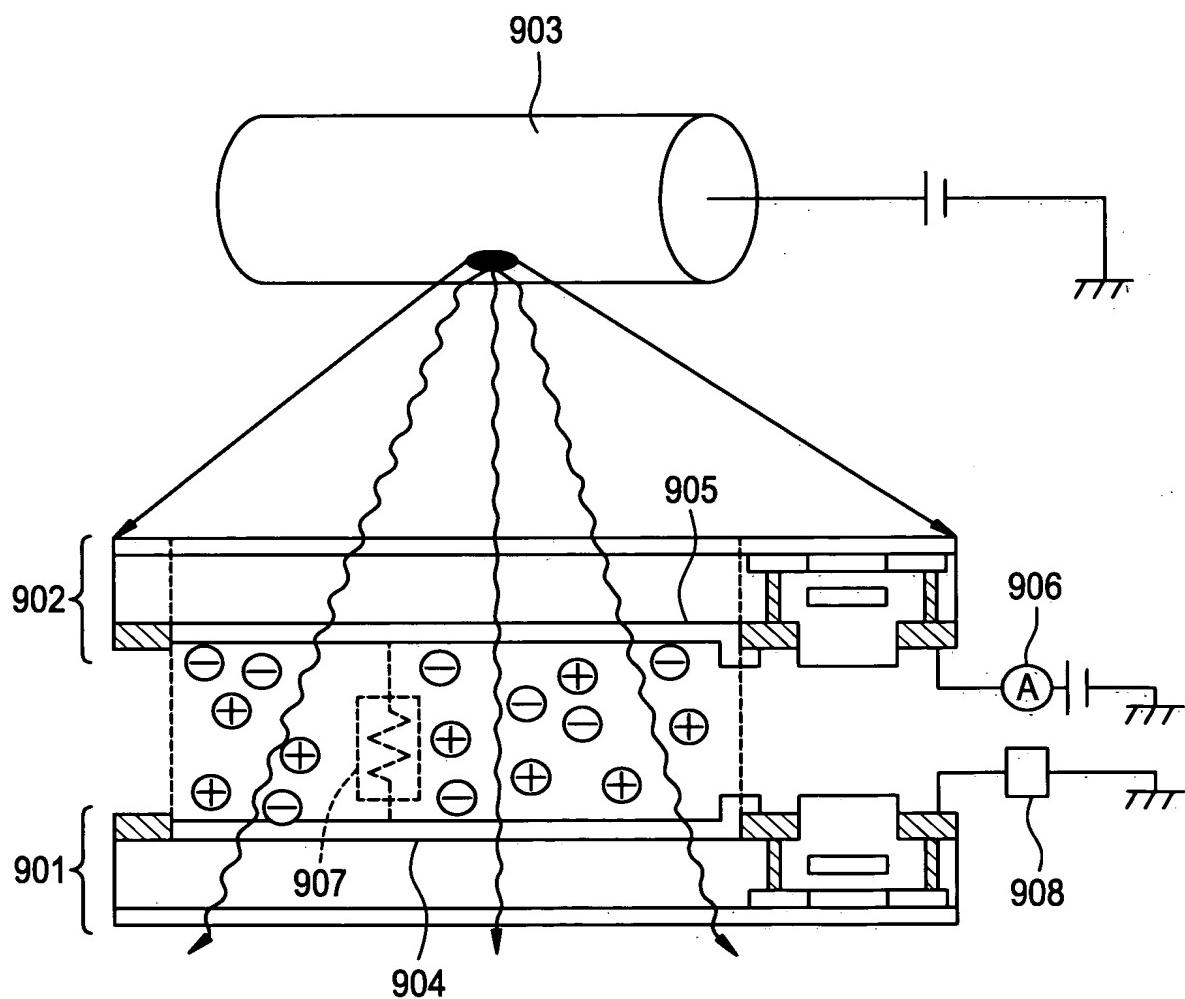


**FIG. 8A****FIG. 8B**



11/18

FIG. 9

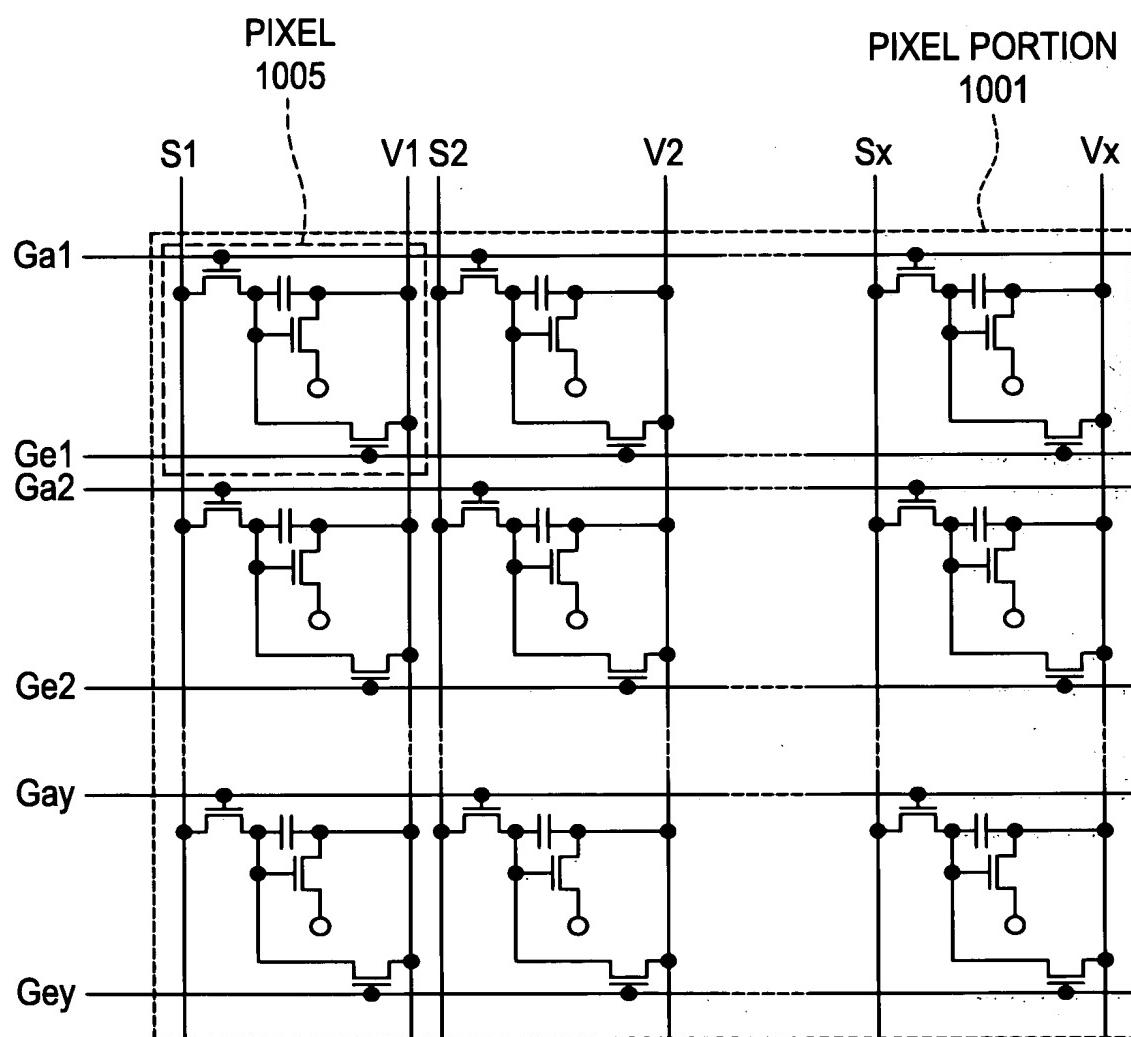


09/866, 051



12/18

FIG. 10



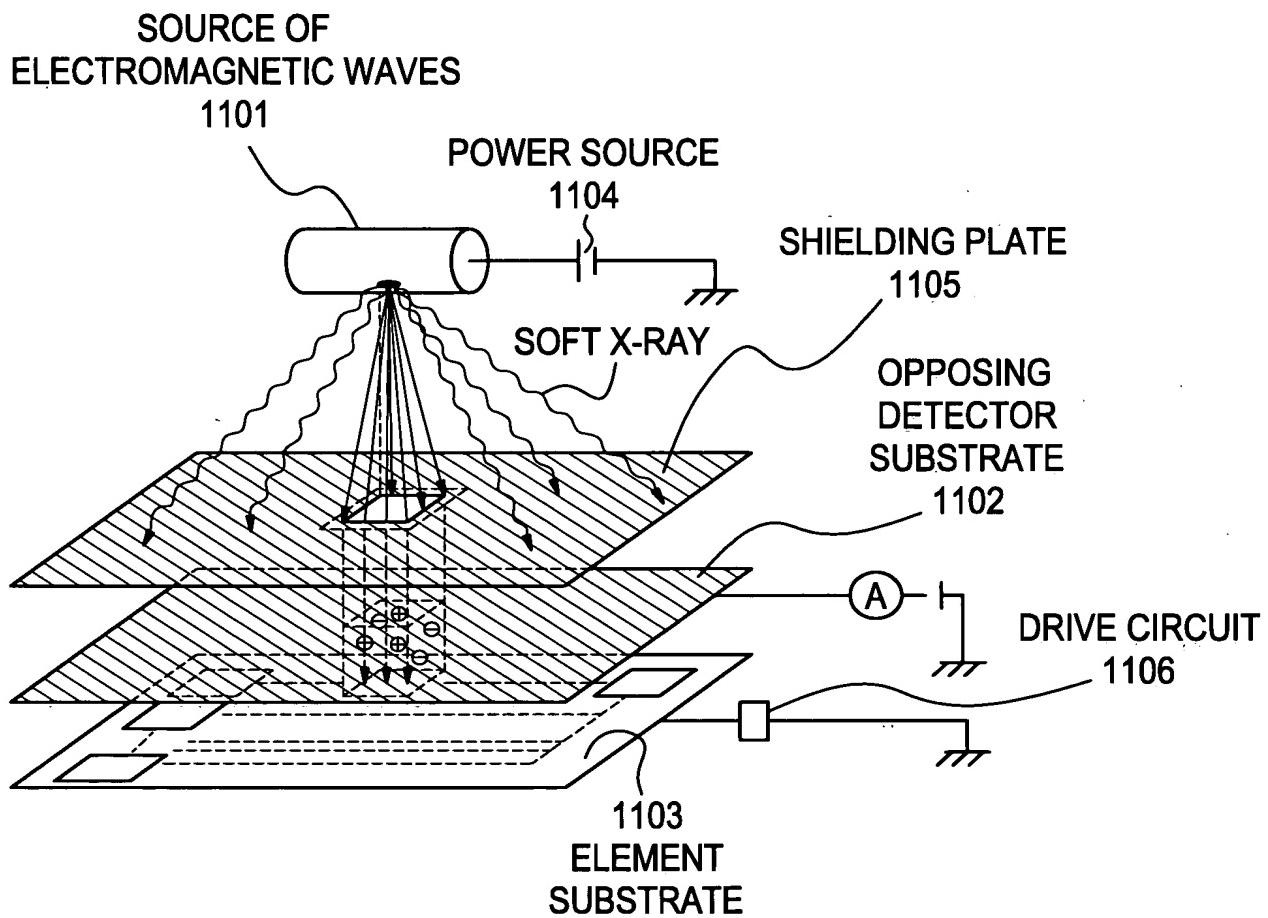
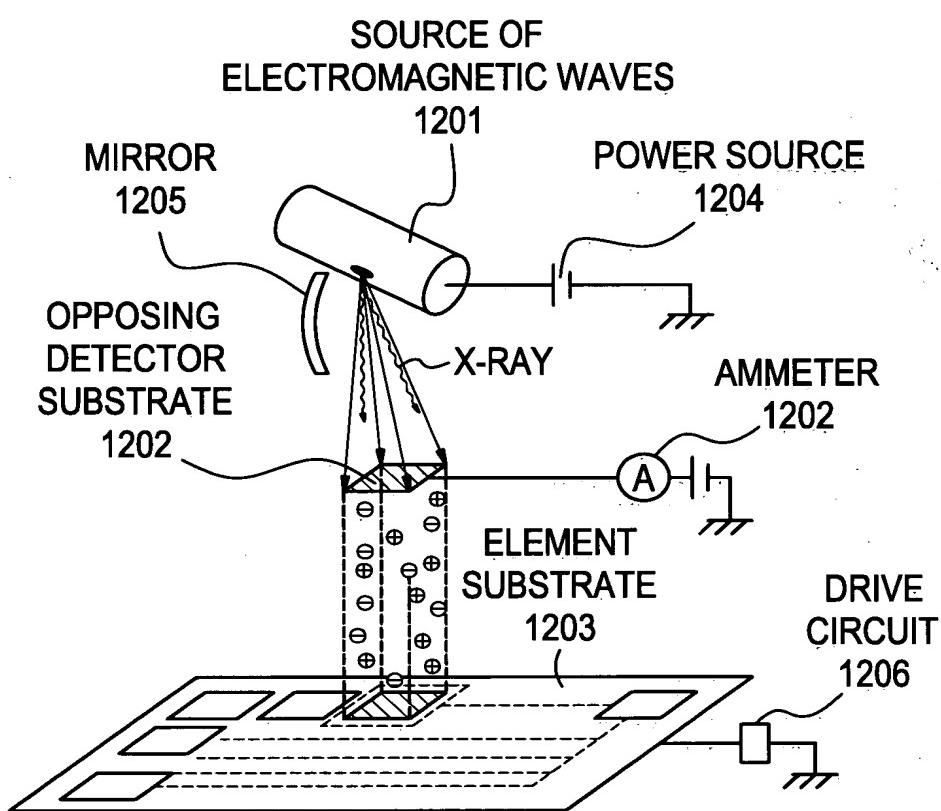
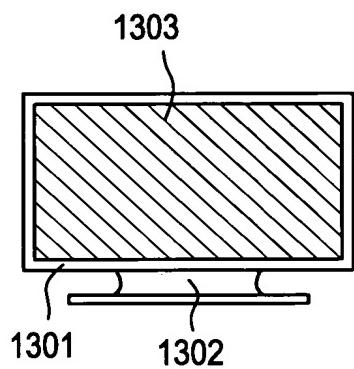
**FIG. 11**

FIG. 12

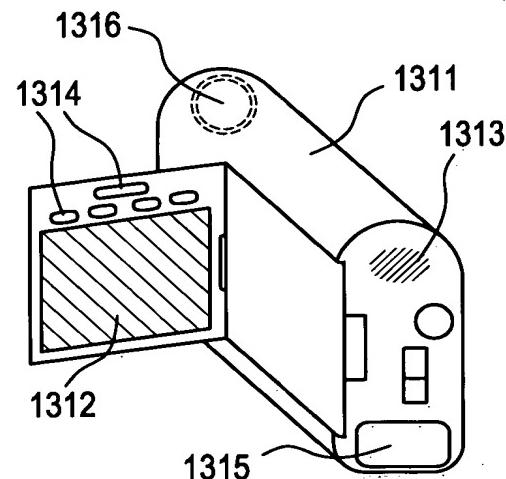


15/18

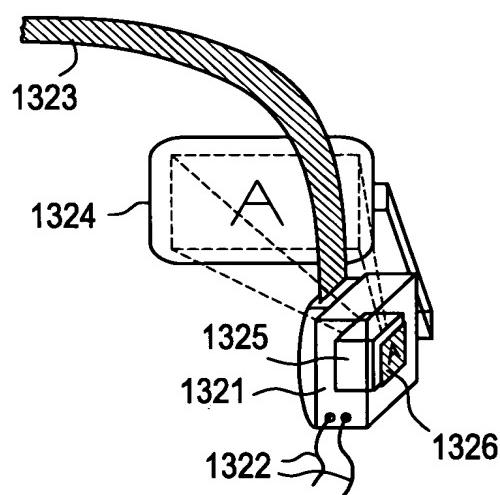
**FIG. 13A**



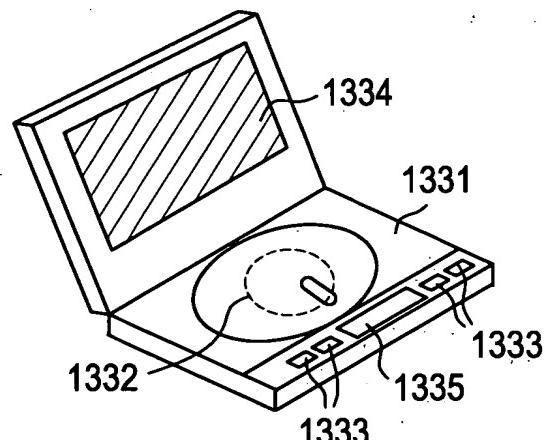
**FIG. 13B**



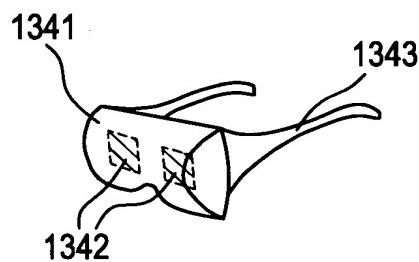
**FIG. 13C**



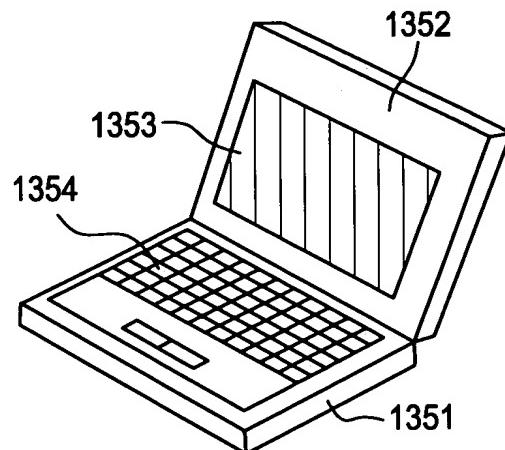
**FIG. 13D**



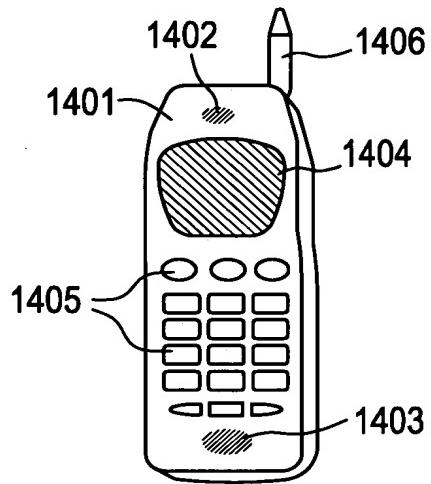
**FIG. 13E**



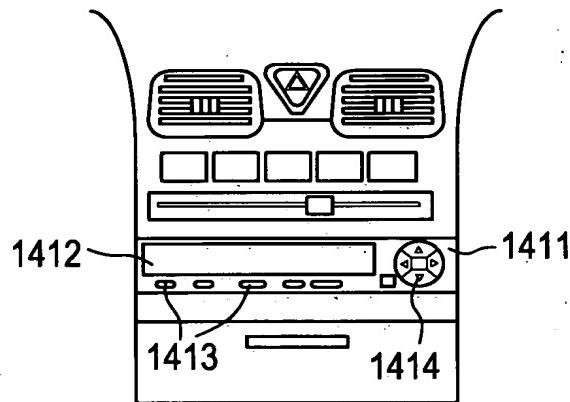
**FIG. 13F**



**FIG. 14A**



**FIG. 14B**



**FIG. 14C**

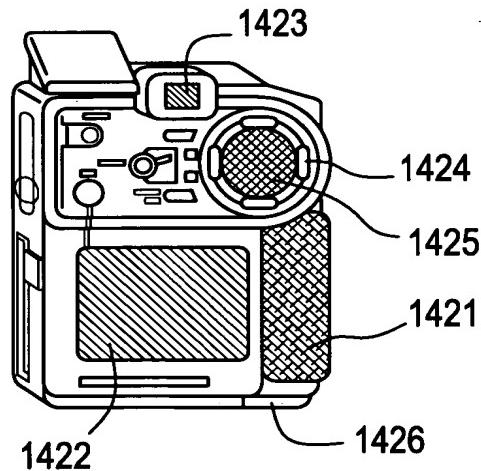
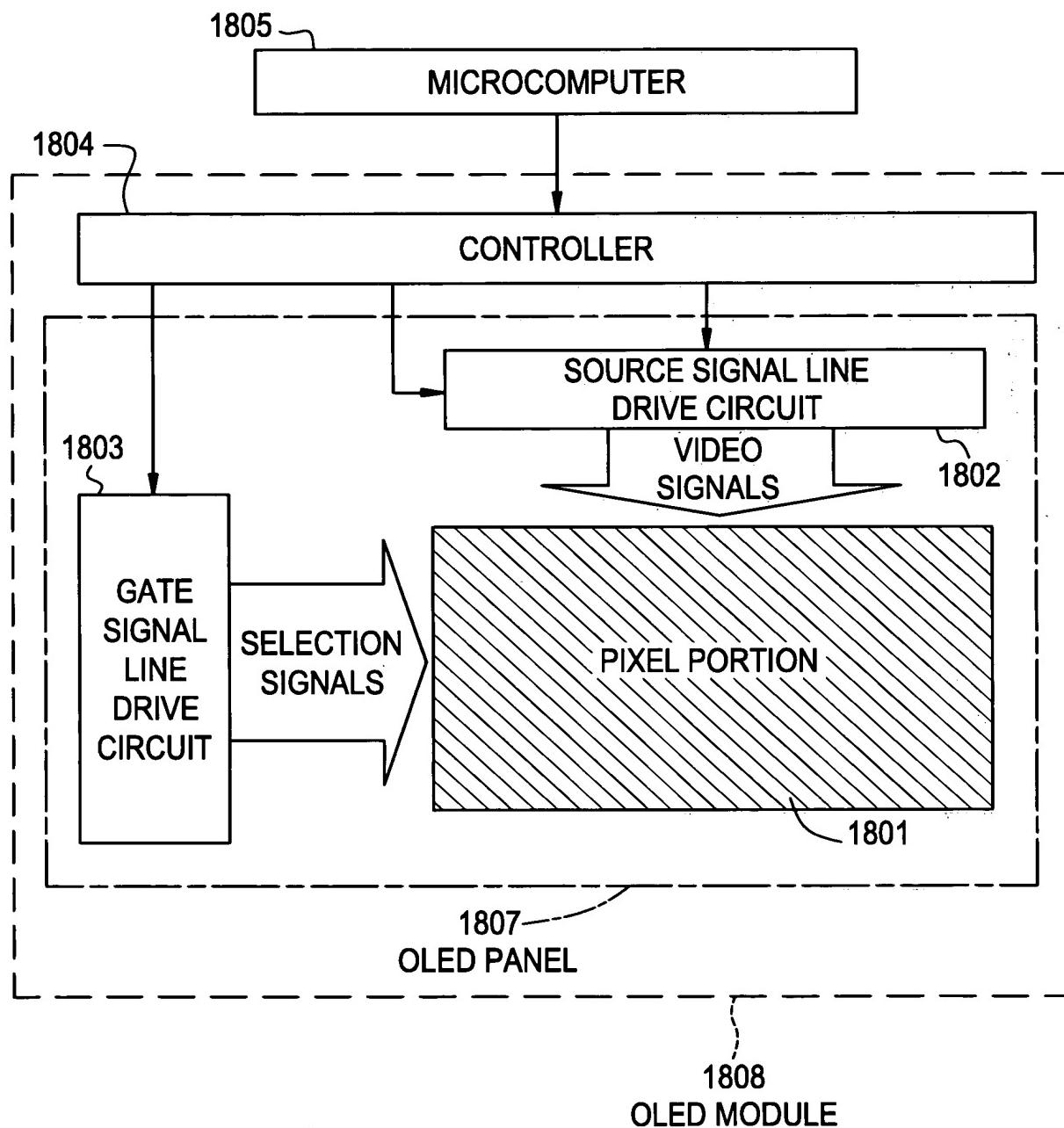




FIG. 15



18/18

FIG. 16A

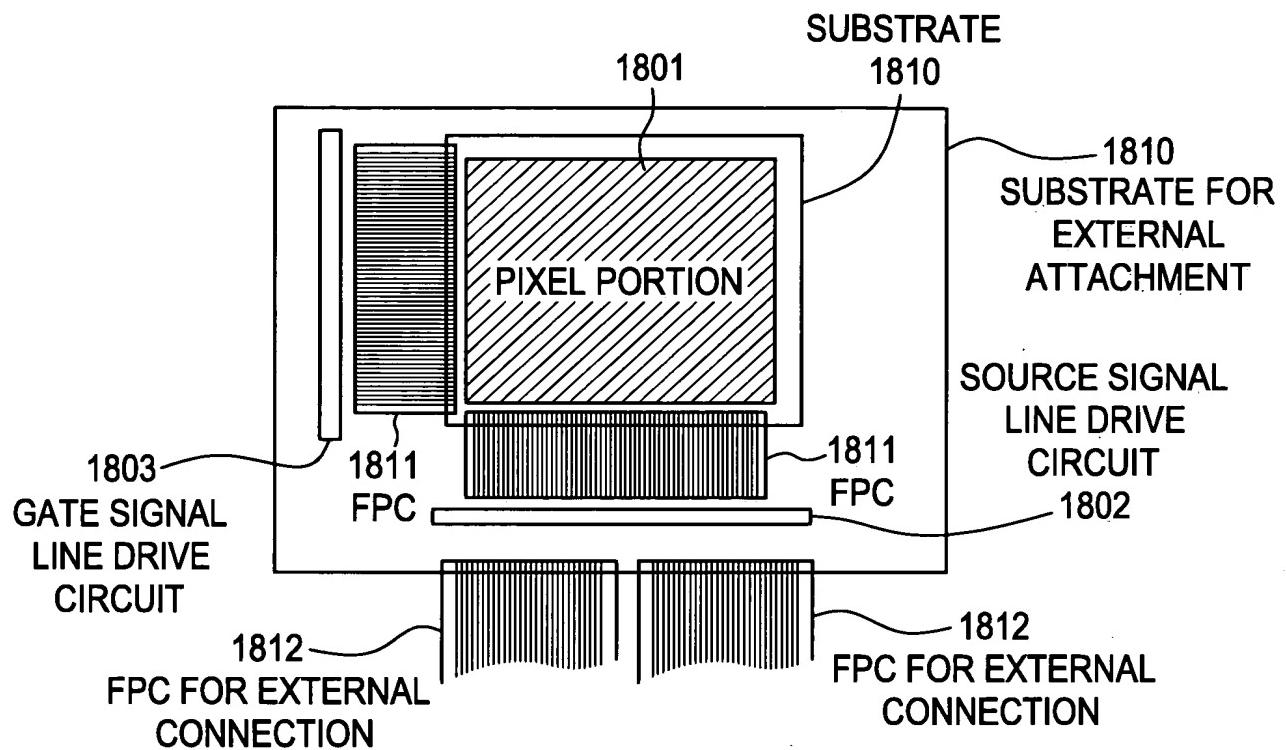


FIG. 16B

